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Patent Application

2771-506

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

OFFICIAL

In re United States Patent Application of:

Applicant: ARNO, Jose, et al.

Application No.: 10/065,219

Date Filed: September 26, 2002

Title: SYSTEM FOR IN-SITU
GENERATION OF FLUORINE
RADICALS AND/OR
FLUORINE-CONTAINING
INTERHALOGEN (XFn)
COMPOUNDS FOR USE IN
CLEANING SEMICONDUCTOR
PROCESSING CHAMBERS

Docket No.: ATMI-506 (7486)

Examiner: WONG, Edna

Art Unit: 1753

Confirmation No.: 9419

Customer No.: 25559

FACSIMILE TRANSMISSION CERTIFICATEATTN: Examiner Edna WONGFax No. (703) 872-9306

I hereby certify that this document is being filed in the United States Patent and Trademark Office, via facsimile transmission to Mail Stop Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on July 7, 2004, to United States Patent and Trademark Office facsimile transmission number (703) 872-9306.

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Number of Pages (including cover)



Tristan Fuierer

July 7, 2004

Date

RESPONSE TO APRIL 9, 2004 OFFICE ACTION
IN UNITED STATES PATENT APPLICATION NO. 10/065,219

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Sir:

This responds to the April 9, 2004 Office Action in the above-identified application.

Patent Application
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Please amend the claims of the application as set out in the following **Section I (Amendments to the Claims)**.

Please amend the drawings of the application as set out in the following **Section II (Amendments to the Drawings)**.

Remarks addressing the various issues raised in the April 9, 2004 Office Action are set out in **Section III (Remarks)** hereof.